

	L #	Hits	Search Text	DBs
1	L1	26084	(inkjet or (ink or fluid or liquid) adj2 (jet\$4 or discharg\$4 or printhead or head)).ti,ab.	US-PGPUB; USPAT
2	L2	56643	((substrate or base or support) with (remov\$4 or separat\$6)).ti,ab.	US-PGPUB; USPAT
3	L3	428	1 and 2	US-PGPUB; USPAT
4	L4	5646	((inkjet or ink or fluid or liquid) adj2 (printhead or head)).ti,ab.	US-PGPUB; USPAT
5	L5	126	2 and 4	US-PGPUB; USPAT
6	L6	948	430/320.ccls.	US-PGPUB; USPAT
7	L7	9	3 and 6	US-PGPUB; USPAT
8	L8	22505	((substrate or base or support) near3 (remov\$4 or separat\$6)).ti,ab.	US-PGPUB; USPAT
9	L9	60	4 and 8	US-PGPUB; USPAT
10	L10	1772	347/47,68,70.ccls.	US-PGPUB; USPAT
11	L11	50	2 and 10	US-PGPUB; USPAT
12	L12	32	11 not (7 or 9)	US-PGPUB; USPAT
13	L13	13036	(solubl\$6 or disolv\$6 or elut\$6) with (resin or polymer\$4 or photopolymer\$8 or sacrific\$8 or resist or photoresist or photosensitiv\$8 or path or channel or (photo or light or radiat\$4 or uv or ultraviolet) adj3 (sensitiv\$8 or polymeriz\$8 or polymeris\$8)).ti,ab.	US-PGPUB; USPAT

	L #	Hits	Search Text	DBs
14	L14	289	1 and 13	US-PGPUB; USPAT
15	L15	2	6 and 14	US-PGPUB; USPAT
16	L16	3	10 and 13	US-PGPUB; USPAT
17	L17	15	4 and 13	US-PGPUB; USPAT
18	L18	293264	(substrate or base or support) near3 (remov\$4 or separat\$6)	US-PGPUB; USPAT
19	L19	135603	solubl\$6 or dissolv\$6 or elut\$6) with (resin or polymer\$4 or photopolymer\$8 or sacrific\$8 or resist or photoresist or photosensitiv\$8 or path or channel or (photo or light or radiat\$4 or uv or ultraviolet) adj3 (sensitiv\$8 or polymeriz\$8 or polymeris\$8)	US-PGPUB; USPAT
20	L20	1209	18 same 19	US-PGPUB; USPAT
21	L21	33	1 and 20	US-PGPUB; USPAT
22	L22	13	takayama-hidehito.in.	US-PGPUB; USPAT
23	L23	52	mouri-akihiro.in.	US-PGPUB; USPAT
24	L24	14	yamaguchi-nobuhito.in.	US-PGPUB; USPAT
25	L25	3	fukasaka-toshihiro.in.	US-PGPUB; USPAT
26	L26	20	1 and (25 or 22 or 23 or 24)	US-PGPUB; USPAT

	L #	Hits	Search Text	DBs
27	L27	29982	(inkjet or ink or fluid or liquid) adj2 (printhead or head)	EPO; JPO; DERWE NT; IBM_TDB
28	L28	100453	piezoelectric	EPO; JPO; DERWE NT; IBM_TDB
29	L29	3965	27 and 28	EPO; JPO; DERWE NT; IBM_TDB
30	L30	99236	solubl\$6 or dissolv\$6 or elut\$6) with (resin or polymer\$4 or photopolymer\$8 or sacrific\$8 or resist or photoresist or photosensitiv\$8 or path or channel or (photo or light or radiat\$4 or uv or ultraviolet) adj3 (sensitiv\$8 or polymeriz\$8 or polymeris\$8)	EPO; JPO; DERWE NT; IBM_TDB
31	L31	9	29 and 30	EPO; JPO; DERWE NT; IBM_TDB
32	L32	106740	(substrate or base or support) near3 (remov\$4 or separat\$6)	EPO; JPO; DERWE NT; IBM_TDB
33	L33	58	29 and 32	EPO; JPO; DERWE NT; IBM_TDB

	L #	Hits	Search Text	DBs
34	L34	55	33 not 31	EPO; JPO; DERWE NT; IBM_TDB